



**Location**

TU Vienna

**Business**

Plasma Technology

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**Workshop on Dry Processing for Nanoelectronics & Micromechanics Deposition & Etching, Presented by Oxford Instruments Plasma Technology and TU Vienna. Please see below for confirmed talk titles.**

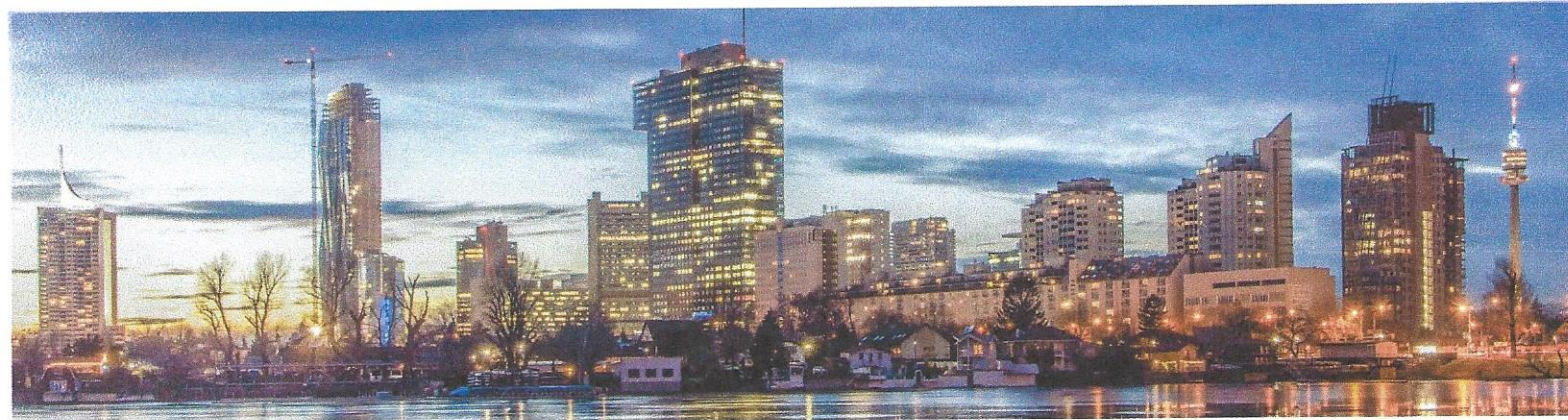
**Tuesday 17 September 2019**

**Wednesday 18 September 2019**

Talk Title	Presenter	Organisation
Dry Etching for MEMS Applications	Dr Zhong	Oxford

Talk Title	Presenter	Organisation
Etching of InP & GaAs by Ion beam	Dr	Oxford





## Wednesday 18 September 2019

Time	Topic	Speaker
09.30 h – 10.00 h	Etching of InP & GaAs by Ion beam Etching	Dr Sebastien Pochon, Oxford Instruments
10.00 h – 10.30 h	Investigation of the Transition Layer Properties of Plasma Oxidized SiC-SiO <sub>2</sub> Stacks	Gernot Fleckl, TU Wien - ISAS
10.30 h – 11.00 h	Silicon Etching for Low Loss Integrated Photonics Components	Dr Zhong Ren Oxford Instruments
11.00 h – 11.15 h	COFFEE BREAK	
11.15 - 11.45	Efficient Plasma Cleaning for PECVD	Dr Owain Thomas, Oxford Instruments
11.45 h – 12.15h	ZnO Optoelectronics using Plasma-based Processing	Borislav Hinkov, <i>N. Schrenk</i> FKE und ZMNS, TU Wien
12.15 h – 12.45 h	Diamond Etching – Applications & Challenges	Dr Andrew Newton, Oxford Instruments
12.45 h - 13.45 h	LUNCH BREAK	
13.45 h – 14.15 h	GaN Low Damage Etch by ICP RIE & ALE	Dr Matthew Loveday – Oxford Instruments
14.15 h – 14.45 h	End Point for Ion Beam Applications Including Etching of Magnetic Materials	Dr Sebastien Pochon, Oxford Instruments
14.45 h – 15.15 h	Double-metal Waveguide Fabrication for High Performance THz QCLs	<i>Martin Keinz</i> , u. ZMNS, TU Wien <i>M. Jaidl</i>
15.15 h – 15.30 h	COFFEE BREAK	
15.30 h - 16:00 h	Fabrication of Biomedical Devices: An Overview of Relevant Plasma Processing Technology	Dr Harm Knoops – Oxford Instruments
16.00 h – 16.30 h	Ion Beam Deposition of Nanolayers of VOx & other Materials	Dr Sebastien Pochon, Oxford Instruments
16.30 h	Final Discussion	